

FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)			ATTY DOCKET NO. 1960.30 DIV. I	APPLICATION NO. NYA 09/773674	PTO S. 3674 C841 U.S. 09/773674 D2/02/01		
Date Submitted to PTO: February 2, 2001			APPLICANT TIMOTHY M. RICHARDSONI	FILING DATE February 2, 2001	GROUP 2877		
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLAS S	FILING DATE IF APPROPRIATE	
<i>N.B.</i>	4,056,376	10/77	Daberko	350	10		
<i>N.B.</i>	5,622,796	4/97	Canestrari, et al.	430	22		
<i>N.R.</i>	4,616,241	10/86	Biefeld, et al.	357	16		
<i>N.R.</i>	4,947,223	8/90	Biefeld, et al.	357	30		
<i>N.R.</i>	5,027,178	6/91	Svilans	357	30		
<i>N.J.</i>	5,608,519	3/97	Gourley, et al.	356	318		
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES/NO/ OR ABSTRACT	
<i>N.J.</i>	0,214,1601	5/90	Europe	G01B	7/34	Abstract	
<i>N.J.</i>	2,702,277	9/94	France	G01M	11/00	<hr/>	
OTHER DOCUMENT(S) (including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER <i>W.A. Brown</i>			DATE CONSIDERED		27 Oct 2004		

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)		ATTY DOCKET NO. 1960.30 DIV. I	APPLICATION NO. NYA 09/773679 PRO
Date Submitted to PTO: February 2, 2001		APPLICANT TIMOTHY M. RICHARDSONI	FILING DATE February 2, 2001
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)			
<i>W.J.</i>	Electro-Optical Systems Design; OTF Quantitative Image Analysis; David Smith, Dec. 1979.		
<i>W.B.</i>	Cambridge University Press; Nanofabrication And Biosystems, H. Hoch, L.W. Jelinski, and H.G. Craighead.		
<i>W.D.</i>	Development In Semiconductor Microlithography; Testing The Mann Type 4800DSW™ Wafer Stepper™, W. Schneider, vol. 174, pp. 6-14 (1979)		
<i>W.B.</i>	JENOPTIK, Laser Optik Systeme		
<i>W.D.</i>	"Contrast Transfer In Confocal Microscopy" by R. Oldenbourg, et al.		
EXAMINER <i>W.A. Bl</i>	DATE CONSIDERED <i>23 Oct 2004</i>		

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 509; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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